-	39		USPAT;	2004/03/02 14:34
		photosensitive photo-sensitive (sensitive	US-PGPUB;	
		near (photo light energy radiation)))	EPO; JPO;	
		with ((reduc\$5 chemical-reduc\$5	DERWENT	
		chemically-reduc\$5 chemical\$3 adj reduc\$5)		
		near2 (plasma gas)) with (treat\$3		
		treatment)		
_	9436	etch\$5 with (passivat\$5 ((so2 "so.sub.2"	USPAT;	2004/03/02 14:44
		sulfur adj dioxide) with (o2 "o.sub.2"	US-PGPUB;	
'		oxygen)))	EPO; JPO;	
			DERWENT	
_	15672	((reduc\$5 chemical-reduc\$5	USPAT;	2004/03/02 15:23
		chemically-reduc\$5 chemical\$3 adj reduc\$5)	US-PGPUB;	*.
		near2 (plasma gas)) with (h2 "h.sub.2"	EPO; JPO;	
		hydrogen nh3 "nh.sub.3" ammonia	DERWENT	
1		hydrogen-generat\$5 h2-generat\$5		
	·	h-generat\$5 "h.sub.2"-generat\$5)		
_	0		USPAT;	2004/03/02 14:46
	ľ	photosensitive photo-sensitive (sensitive	US-PGPUB;	2001, 00, 02 11110
		near (photo light energy radiation)))	EPO; JPO;	
		same (etch\$5 with (passivat\$5 ((so2	DERWENT	
		"so.sub.2" sulfur adj dioxide) with (o2	DELINE	
		"o.sub.2" oxygen)))) same (((reduc\$5		
		chemical-reduc\$5 chemically-reduc\$5		
		chemical=leduc\$5 chemically=leduc\$5 chemical\$3 adj reduc\$5) near2 (plasma		
		gas)) with (h2 "h.sub.2" hydrogen nh3		
		"nh.sub.3" ammonia hydrogen-generat\$5		
,		h2-generat\$5 h-generat\$5		1
		"h.sub.2"-generat\$5))	HODAM -	2004/03/02 14-43
_	4	(USPAT;	2004/03/02 14:43
		sulfur adj dioxide) with (o2 "o.sub.2"	US-PGPUB;	
		oxygen)))) same (((reduc\$5	EPO; JPO;	
		chemical-reduc\$5 chemically-reduc\$5	DERWENT	
		chemical\$3 adj reduc\$5) near2 (plasma		
		gas)) with (h2 "h.sub.2" hydrogen nh3		
		"nh.sub.3" ammonia hydrogen-generat\$5		
		h2-generat\$5 h-generat\$5		
		"h.sub.2"-generat\$5))		
_	10866		USPAT;	2004/03/02 14:52
		"so.sub.2" sulfur adj dioxide) with (o2	US-PGPUB;	1
		"o.sub.2" oxygen)))	EPO; JPO;	
			DERWENT	
-	590		USPAT;	2004/03/02 14:46
		photosensitive photo-sensitive (sensitive	US-PGPUB;	· .
		near (photo light energy radiation)))	EPO; JPO;	,
		same (etch\$5 with (passivat\$5 ((so2	DERWENT	
		"so.sub.2" sulfur adj dioxide) with (o2		
		"o.sub.2" oxygen)))) same ((plasma gas)		
		with (passivat\$5 ((so2 "so.sub.2" sulfur		
		adj dioxide) with (o2 "o.sub.2" oxygen))))		
-	334	1 '	USPAT;	2004/03/02 14:51
		photosensitive photo-sensitive (sensitive	US-PGPUB;	
		near (photo light energy radiation)))	EPO; JPO;	
		with (etch\$5 with (passivat\$5 ((so2	DERWENT	
		"so.sub.2" sulfur adj dioxide) with (o2		
		"o.sub.2" oxygen)))) with ((plasma gas)		
		with (passivat\$5 ((so2 "so.sub.2" sulfur		
		adj dioxide) with (o2 "o.sub.2" oxygen))))		
-	. 5972		USPAT;	2004/03/02 14:51
		photosensitive photo-sensitive (sensitive	US-PGPUB;	
		near (photo light energy radiation)))	EPO; JPO;	
		near2 oxide	DERWENT	

-		9	((resist photoresist photo-resist	USPAT;	2004/03/02 14:51
			photosensitive photo-sensitive (sensitive	US-PGPUB;	•
			<pre>near (photo light energy radiation)))</pre>	EPO; JPO;	
		1	same (etch\$5 with (passivat\$5 ((so2	DERWENT	
			"so.sub.2" sulfur adj dioxide) with (o2		,
			"o.sub.2" oxygen)))) same ((plasma gas)		
			with (passivat\$5 ((so2 "so.sub.2" sulfur		
	1		adj dioxide) with (o2 "o.sub.2"		
			oxygen))))) same ((resist photoresist	-	}
			photo-resist photosensitive		
			photo-sensitive (sensitive near (photo		
			light energy radiation))) near2 oxide)		0004/00/00 14 50
-		1989	(plasma gas) with (passivat\$5 ((so2	USPAT;	2004/03/02 14:53
			"so.sub.2" sulfur adj dioxide) with (o2	US-PGPUB;	
			"o.sub.2" oxygen))) with (etch\$5	EPO; JPO;	
			transfer\$5 pattern\$3)	DERWENT	0004/00/00 14 54
_		0	(resist photoresist photo-resist	USPAT;	2004/03/02 14:54
			photosensitive photo-sensitive (sensitive	US-PGPUB;	
			near (photo light energy radiation)))	EPO; JPO;	
	l		with (((reduc\$5 chemical-reduc\$5	DERWENT	
			chemically-reduc\$5 chemical\$3 adj reduc\$5)		
		1	near2 (plasma gas)) with (h2 "h.sub.2"		
			hydrogen nh3 "nh.sub.3" ammonia		
			hydrogen-generat\$5 h2-generat\$5		
			h-generat\$5 "h.sub.2"-generat\$5)) with		
			((plasma gas) with (passivat\$5 ((so2		
			"so.sub.2" sulfur adj dioxide) with (o2		
			"o.sub.2" oxygen))) with (etch\$5		
		0	transfer\$5 pattern\$3)) (resist photoresist photo-resist	USPAT;	2004/03/02 14:54
_		. 0	photosensitive photo-sensitive (sensitive	US-PGPUB;	2004/05/02 14.54
			near (photo light energy radiation)))	EPO; JPO;	
			same (((reduc\$5 chemical-reduc\$5	DERWENT	·
	1		chemically-reduc\$5 chemical\$3 adj reduc\$5)	DERWEIT	
			near2 (plasma gas)) with (h2 "h.sub.2"		·
		,	hydrogen nh3 "nh.sub.3" ammonia		
			hydrogen-generat\$5 h2-generat\$5		
			h-generat\$5 "h.sub.2"-generat\$5)) same		-
			((plasma gas) with (passivat\$5 ((so2		
			"so.sub.2" sulfur adj dioxide) with (o2	1.	
			"o.sub.2" oxygen))) with (etch\$5		
			transfer\$5 pattern\$3))		
-		7	(((reduc\$5 chemical-reduc\$5	USPAT;	2004/03/02 14:54
	ĺ		chemically-reduc\$5 chemical\$3 adj reduc\$5)	US-PGPUB;	-
			near2 (plasma gas)) with (h2 "h.sub.2"	EPO; JPO;	
		* *	hydrogen nh3 "nh.sub.3" ammonia	DERWENT	
			hydrogen-generat\$5 h2-generat\$5		
			h-generat\$5 "h.sub.2"-generat\$5)) same		
			((plasma gas) with (passivat\$5 ((so2		
	İ		"so.sub.2" sulfur adj dioxide) with (02		
			"o.sub.2" oxygen))) with (etch\$5		.
			transfer\$5 pattern\$3))	110000	2004/02/02 35 25
-		20	(resist photoresist photo-resist	USPAT;	2004/03/02 15:00
			photosensitive photo-sensitive (sensitive	US-PGPUB;	
	.		near (photo light energy radiation))) and	EPO; JPO;	
			(((reduc\$5 chemical-reduc\$5	DERWENT	
			chemically-reduc\$5 chemical\$3 adj reduc\$5)		
			near2 (plasma gas)) with (h2 "h.sub.2"		
			hydrogen nh3 "nh.sub.3" ammonia		
			hydrogen-generat\$5 h2-generat\$5		
			h-generat\$5 "h.sub.2"-generat\$5)) and ((plasma gas) with (passivat\$5 ((so2		
			"so.sub.2" sulfur adj dioxide) with (o2		
			"o.sub.2" oxygen))) with (etch\$5		
			transfer\$5 pattern\$3))		
_	-	2	(stabiliz\$5 with high with aspect with	USPAT;	2004/03/02 15:00
		2	ratio) same ((reduc\$5 chemical-reduc\$5	US-PGPUB;	10,00
			chemically-reduc\$5 chemical\$3 adj reduc\$5)	EPO; JPO;	
			near2 (plasma gas))	DERWENT	
No. 2010 1010 1010 1010			· · · · · · · · · · · · · · · · · · ·		

		79	stabiliz\$5 with high with aspect with ratio	USPAT; US-PGPUB; EPO; JPO;	2004/03/02 15:00
			·	DERWENT	
-		2	(resist photoresist photo-resist	USPAT;	2004/03/02 15:04
			photosensitive photo-sensitive (sensitive	US-PGPUB;	
			near (photo light energy radiation)))	EPO; JPO;	
			with ((reduc\$5 chemical-reduc\$5	DERWENT	
			chemically-reduc\$5 chemical\$3 adj reduc\$5)	,	
	,		near2 (plasma gas)) with (stabiliz\$5 with high with aspect with ratio)		
	,	2	(resist photoresist photo-resist	USPAT;	2004/03/02 15:05
		۷	photosensitive photo-sensitive (sensitive	US-PGPUB;	2004/03/02 15:05
			near (photo light energy radiation)))	EPO; JPO;	
			same ((reduc\$5 chemical-reduc\$5	DERWENT	
			chemically-reduc\$5 chemical\$3 adj reduc\$5)		•
			near2 (plasma gas)) same (stabiliz\$5 with		
		0.500	high with aspect with ratio)		
_		8529	430/311,313,314,316,317.ccls. 438/710.ccls. 216/67.ccls. 134/1.2.ccls.	USPAT;	2004/03/02 15:05
			436/710.CCIS. 216/67.CCIS. 134/1.2.CCIS.	US-PGPUB; EPO; JPO;	
				DERWENT	
		616	((reduc\$5 chemical-reduc\$5	USPAT;	2004/03/02 15:06
			chemically-reduc\$5 chemical\$3 adj reduc\$5)	US-PGPUB;	
			near2 (plasma gas)) and	EPO; JPO;	*
			(430/311,313,314,316,317.ccls.	DERWENT .	
	ĺ	150	438/710.ccls. 216/67.ccls. 134/1.2.ccls.)		,
_		152	(chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)	USPAT;	2004/03/02 15:17
			chemicals adj reduces, hearz (plasma gas)	US-PGPUB; EPO; JPO;	
				DERWENT	
-		2	(resist photoresist photo-resist	USPAT;	2004/03/02 15:09
			photosensitive photo-sensitive (sensitive	US-PGPUB;	
			near (photo light energy radiation)))	EPO; JPO;	
			with ((chemical-reduc\$5 chemically-reduc\$5	DERWENT	
			chemical\$3 adj reduc\$5) near2 (plasma		
_		2	gas)) (resist photoresist photo-resist	USPAT;	2004/03/02 15:09
		_	photosensitive photo-sensitive (sensitive	US-PGPUB;	2004/03/02 13:09
			near (photo light energy radiation)))	EPO; JPO;	
			same ((chemical-reduc\$5 chemically-reduc\$5	DERWENT	
	•	•	chemical\$3 adj reduc\$5) near2 (plasma		
		1.0	gas))		
-		19	((resist photoresist photo-resist photosensitive photo-sensitive (sensitive	USPAT;	2004/03/02 15:10
			near (photo light energy radiation)))	US-PGPUB; EPO; JPO;	
	.		430/\$.ccls.) and ((chemical-reduc\$5	DERWENT	
			chemically-reduc\$5 chemical\$3 adj reduc\$5)		
	.		near2 (plasma gas))		
		56381	(reduc\$5) near (plasma gas)	USPAT;	2004/03/02 15:22
				US-PGPUB;	
				EPO; JPO;	
_		222	(resist photoresist photo-resist	DERWENT USPAT;	2004/03/02 15:22
}			photosensitive photo-sensitive (sensitive	US-PGPUB;	2001/00/02 13.22
			near (photo light energy radiation)))	EPO; JPO;	
			with ((reduc\$5) near (plasma gas))	DERWENT	
-		1412666	(h2 "h.sub.2" hydrogen nh3 ethylene c2h4	USPAT;	2004/03/02 16:39
	ļ		"c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5	US-PGPUB;	
			nz-generatss n-generatss "h.sub.2"-generat\$5)	EPO; JPO; DERWENT	
_		34	((resist photoresist photo-resist	USPAT;	2004/03/02 15:34
	ļ		photosensitive photo-sensitive (sensitive	US-PGPUB;	2001/00/02 10.04
			near (photo light energy radiation))	EPO; JPO;	
	. 1		with ((reduc\$5) near (plasma gas))) with (DERWENT	
			(h2 "h.sub.2" hydrogen nh3 ethylene c2h4		
			"c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5		
			"h.sub.2"-generat\$5))		
			gonoracyo//		I

_	435139	(polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer	USPAT; US-PGPUB;	2004/03/02 15:35
		film coating underlayer material	EPO; JPO;	
		under-layer under adj layer)	DERWENT	
_	2	((polymer polymeric organic novolac	USPAT;	2004/03/02 15:46
ĺ	_	novolak low-k adj dielectric silk) near	US-PGPUB;	
		(layer film coating underlayer material	EPO; JPO;	
		under-layer under adj layer)) with	DERWENT	
		((chemical-reduc\$5 chemically-reduc\$5		
		chemical\$3 adj reduc\$5) near2 (plasma		
		gas))	HCDAM -	2004/03/02 15:41
-	.6	((polymer polymeric organic novolac	USPAT; US-PGPUB;	2004/03/02 13.41
1		novolak low-k adj dielectric silk) near	EPO; JPO;	
		(layer film coating underlayer material under-layer under adj layer)) same	DERWENT	Ì
		((chemical-reduc\$5 chemically-reduc\$5	DEIGNERT	
		chemical=leduc\$5 chemically raddays		
		qas))		
	88530	(h2 "h.sub.2" hydrogen nh3 ethylene c2h4	USPAT;	2004/03/02 15:45
-	00000	"c.sub.2 h.sub.4" hydrogen-generat\$5	US-PGPUB;	
		h2-generat\$5 h-generat\$5	EPO; JPO;	
		"h.sub.2"-generat\$5) near (plasma gas)	DERWENT	
_	299	((polymer polymeric organic novolac	USPAT;	2004/03/02 15:49
		novolak low-k adj dielectric silk) near	US-PGPUB;	
		(layer film coating underlayer material	EPO; JPO;	
		under-layer under adj layer)) with ((h2	DERWENT	
		"h.sub.2" hydrogen nh3 ethylene c2h4		
		"c.sub.2 h.sub.4" hydrogen-generat\$5		
		h2-generat\$5 h-generat\$5		
	1.0	"h.sub.2"-generat\$5) near (plasma gas)) ((polymer polymeric organic novolac	USPAT;	2004/03/02 15:46
_	19	novolak low-k adj dielectric silk) near	US-PGPUB;	
		(layer film coating underlayer material	EPO; JPO;	
		under-layer under adj layer)) with ((h2	DERWENT	
		"h.sub.2" hydrogen nh3 ethylene c2h4		
		"c.sub.2 h.sub.4" hydrogen-generat\$5		
		h2-generat\$5 h-generat\$5		
	1	"h.sub.2"-generat\$5) near (plasma gas))		
		with (resist photoresist photo-resist		
		photosensitive photo-sensitive (sensitive		
		near (photo light energy radiation)))	HCDATE.	2004/03/02 15:49
_	160	((polymer polymeric organic novolac	USPAT; US-PGPUB;	2004/03/02 13:49
		novolak low-k adj dielectric silk) near	EPO; JPO;	
		(layer film coating underlayer material under-layer under adj layer)) with	DERWENT	
		((reduc\$5) near (plasma gas))		
_	10		USPAT;	2004/03/02 15:49
		novolak low-k adj dielectric silk) near	US-PGPUB;	
		(layer film coating underlayer material	EPO; JPO;	
		under-layer under adj layer)) with	DERWENT	
		((reduc\$5) near (plasma gas)) with (resist		
		photoresist photo-resist photosensitive		
		photo-sensitive (sensitive near (photo		
		light energy radiation)))	HCDAM.	2004/03/02 15:57
-	11		USPAT; US-PGPUB	2004/03/02 13:37
		("20030017711") or ("6528432") or ("5833758") or ("6465159") or ("6562700")	OS EGEOD	
		or ("4904866") or ("5688719") or		
1		("6261951") or ("6444408")).PN.		
_	12	1 (10.00.00.00.00.00.00.00.00.00.00.00.00.0	USPAT;	2004/03/02 15:54
	12	or ("6673721") or ("6562700") or	US-PGPUB	
		("6420098") or ("6225219") or ("6528432")		
1		or ("5833758") or ("6465159") or		
		("6562700") or ("4904866") or		
		("5688719")).PN.		2004/02/00 15 57
-	4	ep-903777-\$.did. jp-2000200832-\$.did.	USPAT;	2004/03/02 15:57
			US-PGPUB;	
			EPO; JPO; DERWENT	
	1		DEIZMENT	

				1—2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2
_	20	(ep-903777-\$.did. jp-2000200832-\$.did.) ((("5985524") or ("20030017420") or ("20030017711") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719") or ("6261951") or ("6444408")).PN.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:57
7 0 0 0 0 0 0 0 0 0 0 0 0 0 0 0 0 0 0 0		((("5985524") or ("6218085") or ("6503840") or ("6673721") or ("6562700") or ("6420098") or ("6225219") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719")).PN.)		
-	10	((ep-903777-\$.did. jp-2000200832-\$.did.) ((("5985524") or ("20030017420") or ("20030017711") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719") or ("6261951") or ("6444408")).PN.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 16:06
		((("5985524") or ("6218085") or ("6503840") or ("6673721") or ("6562700") or ("6420098") or ("6225219") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719")).PN.)) and (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma		
_	10	<pre>gas)) (stabiliz\$5 with high with aspect with ratio))</pre>	USPAT;	2004/03/02 16:27
	10	((ep-903777-\$.did. jp-2000200832-\$.did.) ((("5985524") or ("20030017420") or ("20030017711") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719") or ("6261951") or ("6444408")).PN.) ((("5985524") or ("6218085") or ("6503840") or ("6673721") or ("6562700") or ("6420098") or ("6225219") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719")).PN.)) not ((ep-903777-\$.did. jp-2000200832-\$.did.) ((("5985524") or ("20030017420") or ("20030017711") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719") or ("6261951") or ("6444408")).PN.) ((("5985524") or ("6218085") or ("6503840") or ("6673721") or ("6562700") or ("6562700") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719")).PN.)) and (((reduc\$5 chemical-reduc\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 16:2/
-	2	chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) (stabiliz\$5 with high with aspect with ratio))) ("6114259").PN.	USPAT; US-PGPUB;	2004/03/02 16:27
_	36510	((polymer polymeric organic novolac	EPO; JPO; DERWENT USPAT;	2004/03/02 16:39
		novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4)	US-PGPUB; EPO; JPO; DERWENT	
_	2545	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 16:38

_	5376123	(reduc\$5 chemical-reduc\$5	USPAT;	2004/03/02 16:39
		chemically-reduc\$5 chemical\$3 adj reduc\$5)	US-PGPUB;	
			EPO; JPO;	
	1.410666	(h2 III)h 2II h	DERWENT	2004/03/03 16-20
_	1412666	(h2 "h.sub.2" hydrogen nh3 ethylene c2h4	USPAT;	2004/03/02 16:39
		"c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5	US-PGPUB; EPO; JPO;	
		"h.sub.2"-generat\$5)	DERWENT	
	357	(((polymer polymeric organic novolac	USPAT;	2004/03/02 17:08
	337	novolak low-k adj dielectric silk) near	US-PGPUB;	2001,03,02 17.00
		(layer film coating underlayer material	EPO; JPO;	
		under-layer under adj layer)) with	DERWENT	
		(stabiliz\$5 harden\$3 treat\$4) with (gas		
		plasma)) with (((reduc\$5 chemical-reduc\$5	1	
		chemically-reduc\$5 chemical\$3 adj reduc\$5)		
) ((h2 "h.sub.2" hydrogen nh3 ethylene		
		c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5	'	'
		h2-generat\$5 h-generat\$5		
		"h.sub.2"-generat\$5)))		
-	30	(((polymer polymeric organic novolac	USPAT;	2004/03/02 16:44
		novolak low-k adj dielectric silk) near	US-PGPUB;	
		(layer film coating underlayer material	EPO; JPO; DERWENT	
		under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas	DEVMENT	
		plasma)) with (((reduc\$5 chemical-reduc\$5		
		chemically-reduc\$5 chemical\$3 adj reduc\$5)		
) with ((h2 "h.sub.2" hydrogen nh3		
		ethylene c2h4 "c.sub.2 h.sub.4"		
		hydrogen-generat\$5 h2-generat\$5		
		h-generat\$5 "h.sub.2"-generat\$5)))		
-	31	(((polymer polymeric organic novolac	USPAT;	2004/03/02 17:05
.		novolak low-k adj dielectric silk) near	US-PGPUB;	
		(layer film coating underlayer material	EPO; JPO;	
		under-layer under adj layer)) with	DERWENT	
		(stabiliz\$5 harden\$3 treat\$4) with (gas		
	•	plasma)) with (((reduc\$5 chemical-reduc\$5		
		chemically-reduc\$5 chemical\$3 adj reduc\$5)		
) ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5		-
		h2-generat\$5 h-generat\$5		
		"h.sub.2"-generat\$5))) with (resist		
		photoresist photo-resist photosensitive		
		photo-sensitive (sensitive near (photo		
		light energy radiation)))		
-	28	((((polymer polymeric organic novolac	USPAT;	2004/03/02 17:06
		novolak low-k adj dielectric silk) near	US-PGPUB;	
		(layer film coating underlayer material	EPO; JPO;	
		under-layer under adj layer)) with	DERWENT	
		(stabiliz\$5 harden\$3 treat\$4) with (gas		
		plasma)) with (((reduc\$5 chemical-reduc\$5		
		chemically-reduc\$5 chemical\$3 adj reduc\$5)) ((h2 "h.sub.2" hydrogen nh3 ethylene		
1.		c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5		
		h2-generat\$5 h-generat\$5		
		"h.sub.2"-generat\$5))) with (resist		
		photoresist photo-resist photosensitive		,
		photo-sensitive (sensitive near (photo		
		light energy radiation)))) not		
		((((polymer polymeric organic novolac		
		novolak low-k adj dielectric silk) near		
		(layer film coating underlayer material		
		under-layer under adj layer)) with		
		(stabiliz\$5 harden\$3 treat\$4) with (gas		
		plasma)) with (((reduc\$5 chemical-reduc\$5		
		chemically-reduc\$5 chemical\$3 adj reduc\$5)		
) with ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4"		
		hydrogen-generat\$5 h2-generat\$5		
		h-generat\$5 "h.sub.2"-generat\$5))))		
L	1		1	.4. <u></u>

-	52	((((polymer polymeric organic novolac	USPAT;	2004/03/02 17:08
1		novolak low-k adj dielectric silk) near	US-PGPUB;	
1		(layer film coating underlayer material	EPO; JPO;	ĺ
1		under-layer under adj layer)) with	DERWENT	}
		(stabiliz\$5 harden\$3 treat\$4) with (gas		}
1		plasma)) with (((reduc\$5 chemical-reduc\$5	İ	[
	1	chemically-reduc\$5 chemical\$3 adj reduc\$5)	1	1
) ((h2 "h.sub.2" hydrogen nh3 ethylene		}
		c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5		
1	1	h2-generat\$5 h-generat\$5	İ	
)		"h.sub.2"-generat\$5)))) and (430/\$.ccls.	1	
		438/\$.ccls.)	1	
-	33	(((((polymer polymeric organic novolac	USPAT;	2004/03/02 17:09
ł		novolak low-k adj dielectric silk) near	US-PGPUB;	
	j	(layer film coating underlayer material	EPO; JPO;	
		under-layer under adj layer)) with	DERWENT	}
		(stabiliz\$5 harden\$3 treat\$4) with (gas	22222	
}		plasma)) with (((reduc\$5 chemical-reduc\$5		1
	Ì	chemically-reduc\$5 chemical\$3 adj reduc\$5)		1
-) ((h2 "h.sub.2" hydrogen nh3 ethylene	ļ	
1		c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5	J	[
	1	h2-generat\$5 h-generat\$5		
	İ	"h.sub.2"-generat\$5)))) and (430/\$.ccls.	1	-
		438/\$.ccls.)) not (((((polymer polymeric	Į	
ì		organic novolac novolak low-k adj		. [
}]		ĺ	
		dielectric silk) near (layer film coating	}]
		underlayer material under-layer under adj	}	·
}		layer)) with (stabiliz\$5 harden\$3 treat\$4)		
		with (gas plasma)) with (((reduc\$5	1	l
		chemical-reduc\$5 chemically-reduc\$5	Ì	}
	İ	chemical\$3 adj reduc\$5)) ((h2 "h.sub.2"	}	
		hydrogen nh3 ethylene c2h4 "c.sub.2	ļ	1
		h.sub.4" hydrogen-generat\$5 h2-generat\$5	1	
		h-generat\$5 "h.sub.2"-generat\$5))) with		Į J
		(resist photoresist photo-resist)	
		photosensitive photo-sensitive (sensitive	}	
		near (photo light energy radiation))))	1	1
		not ((((polymer polymeric organic novolac		
	ì	novolak low-k adj dielectric silk) near		
1	ļ	(layer film coating underlayer material		ĺ
		under-layer under adj layer)) with		
	1	(stabiliz\$5 harden\$3 treat\$4) with (gas		
1	1	plasma)) with (((reduc\$5 chemical-reduc\$5		. [
	Į	chemically-reduc\$5 chemical\$3 adj reduc\$5)		1
	Ì) with ((h2 "h.sub.2" hydrogen nh3	{	
	1	ethylene c2h4 "c.sub.2 h.sub.4"		ļ
1	1	hydrogen-generat\$5 h2-generat\$5	1	
]	h-generat\$5 "h.sub.2"-generat\$5)))))		1
		((((polymer polymeric organic novolac	(
[novolak low-k adj dielectric silk) near	ļ	j l
	1	(layer film coating underlayer material		
1	ì	under-layer under adj layer)) with	{	
		(stabiliz\$5 harden\$3 treat\$4) with (gas	1	ļ
Í	1	plasma)) with (((reduc\$5 chemical-reduc\$5]	
	1	chemically-reduc\$5 chemical\$3 adj reduc\$5)		
!) ((h2 "h.sub.2" hydrogen nh3 ethylene	{	
		c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5	{	
	1	h2-generat\$5 h-generat\$5		
	1	"h.sub.2"-generat\$5))) with (resist	1	
J		photoresist photo-resist photosensitive		
		photo-sensitive (sensitive near (photo		
1	1	light energy radiation)))))		
L	J	TIGHT CHELGY LAGIACTOR!	L	<u> </u>